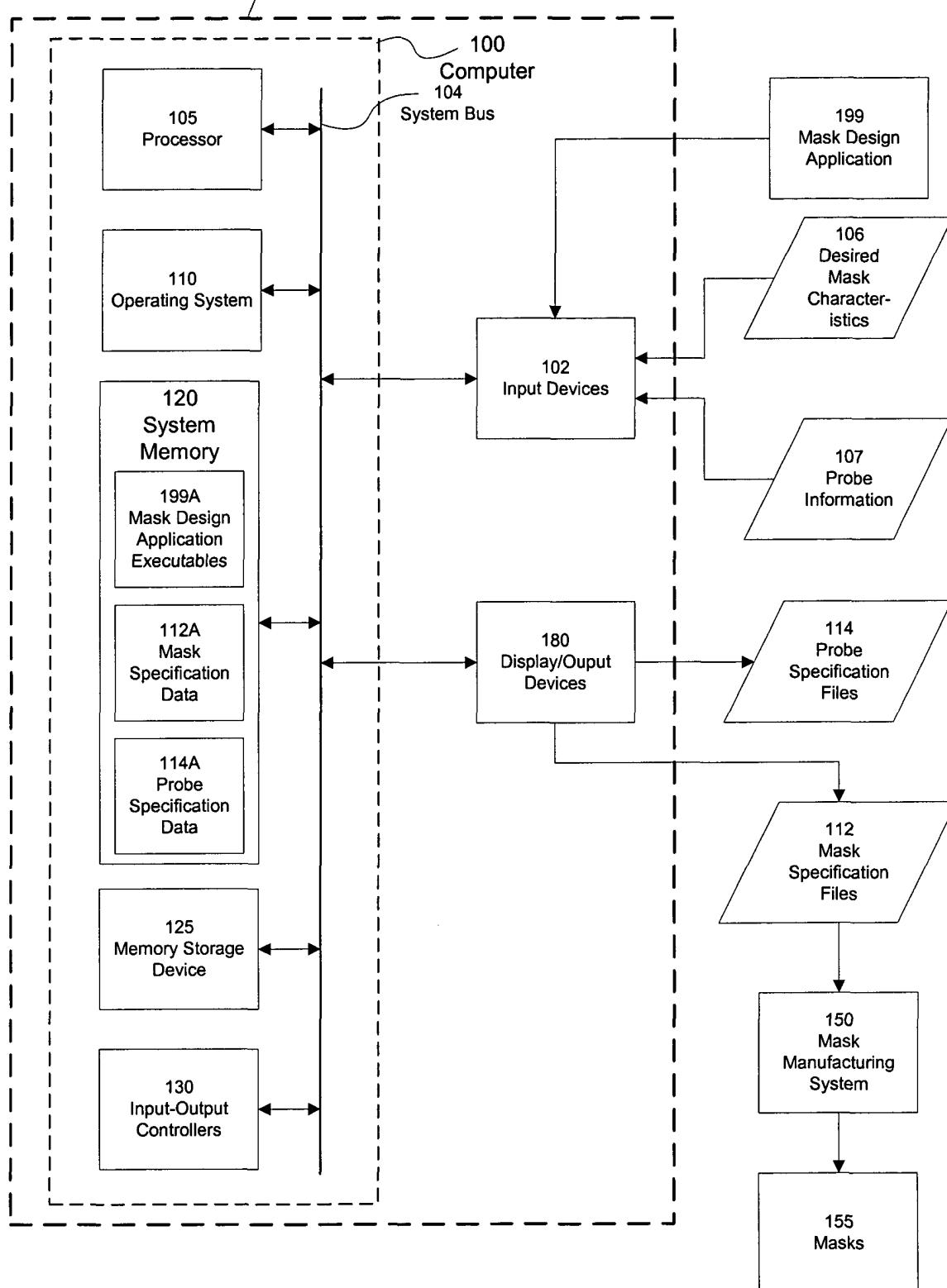


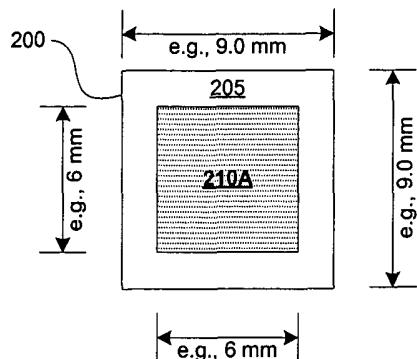
101

## Mask Design System

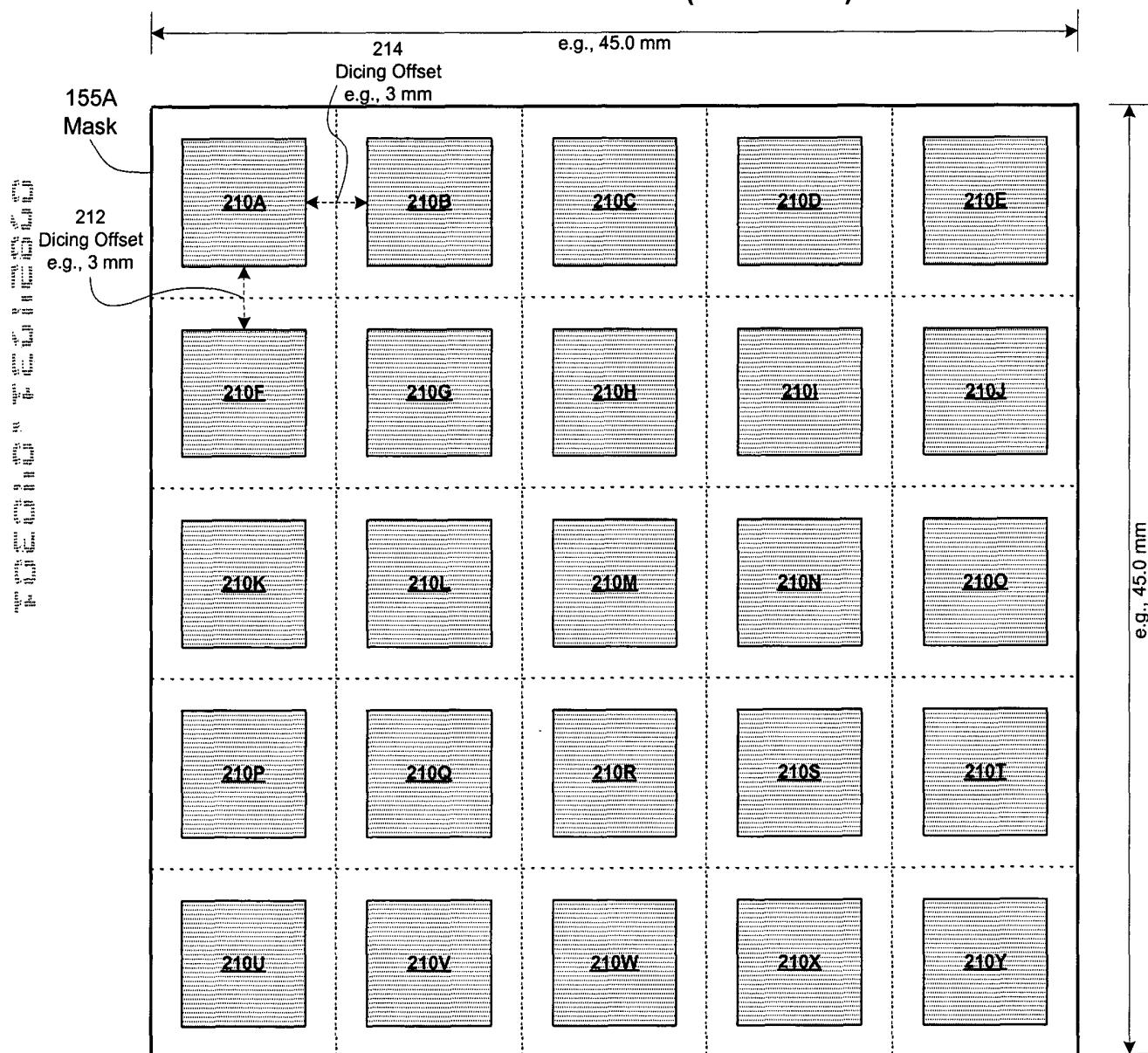
FIGURE 1

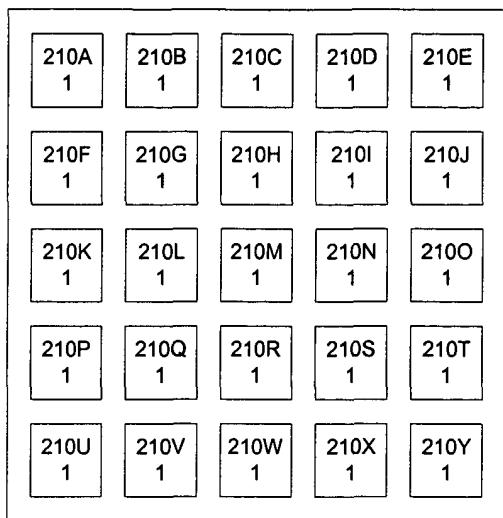
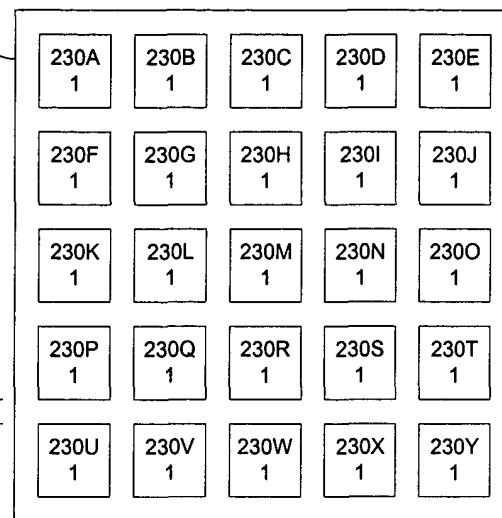
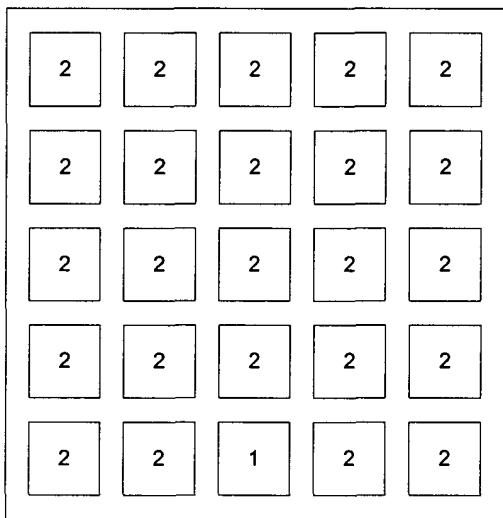
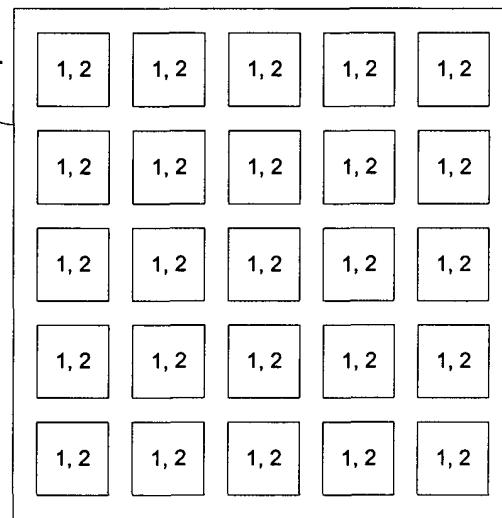
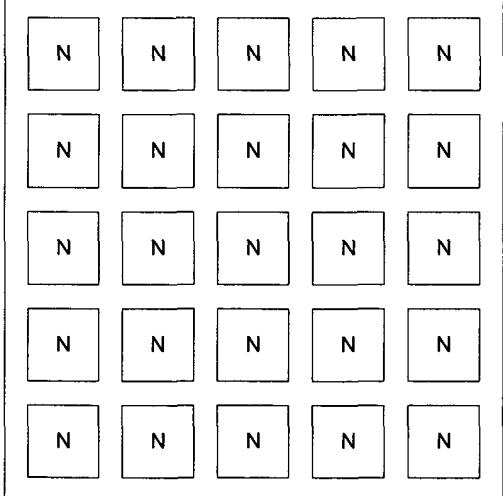
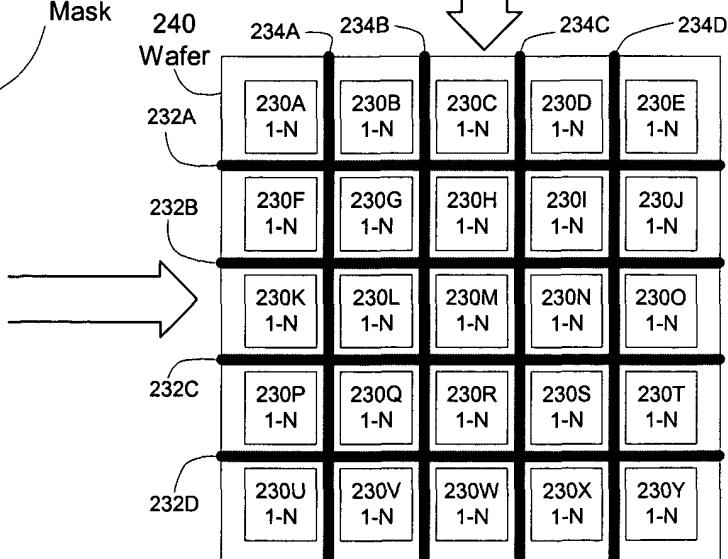


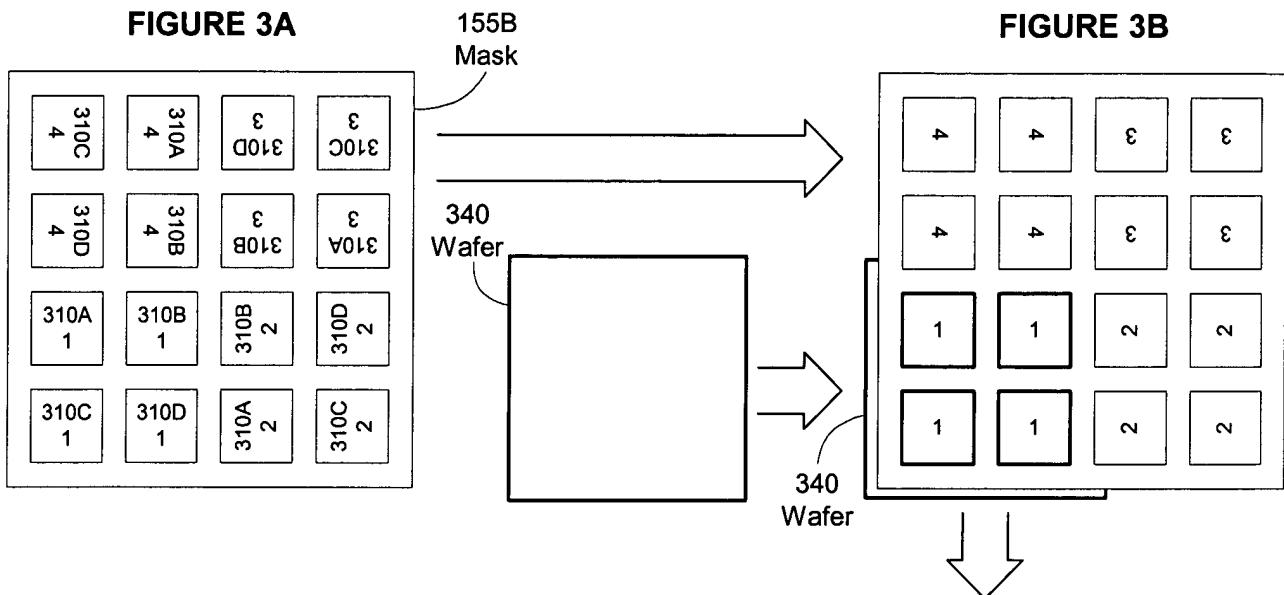
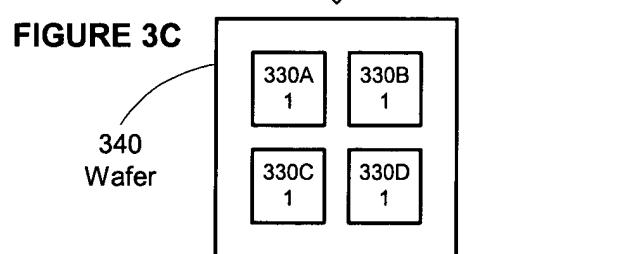
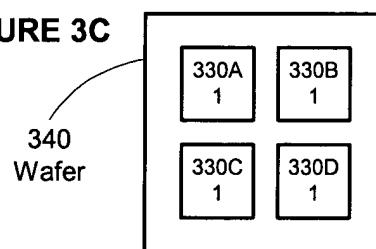
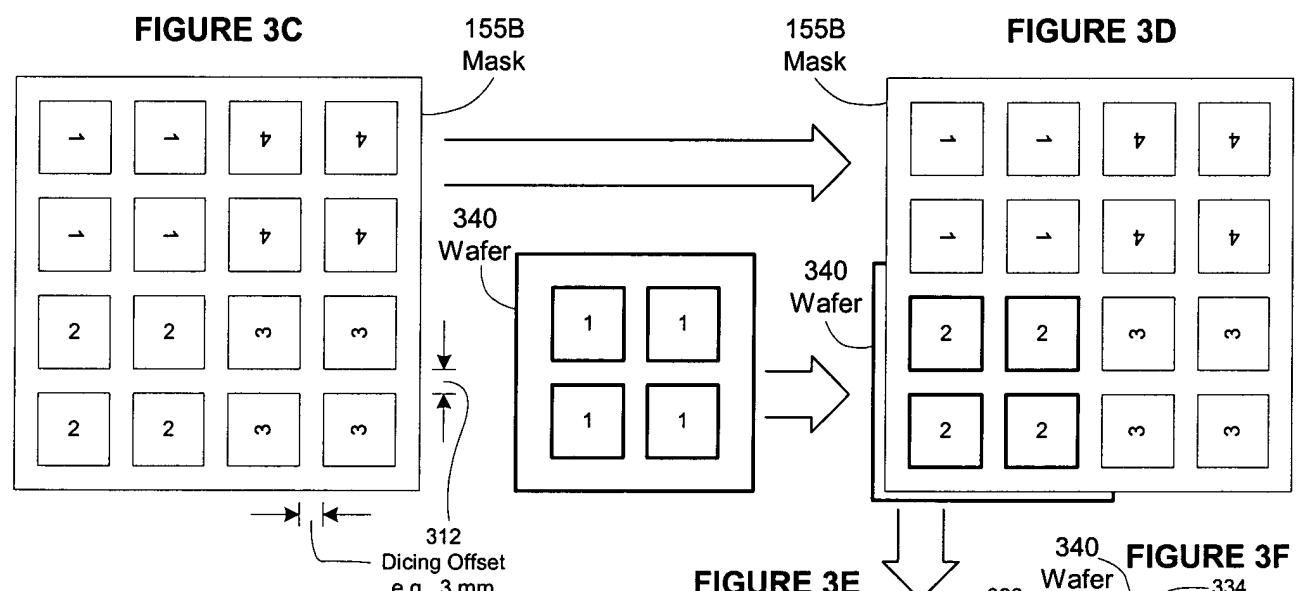
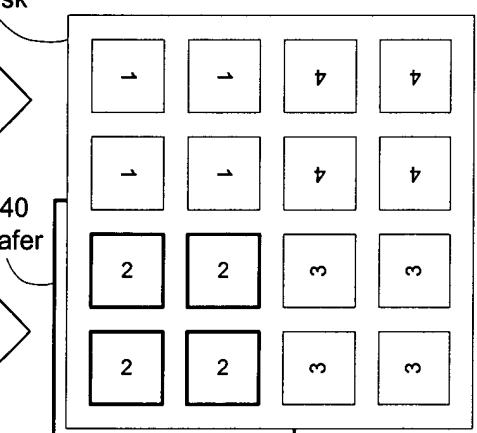
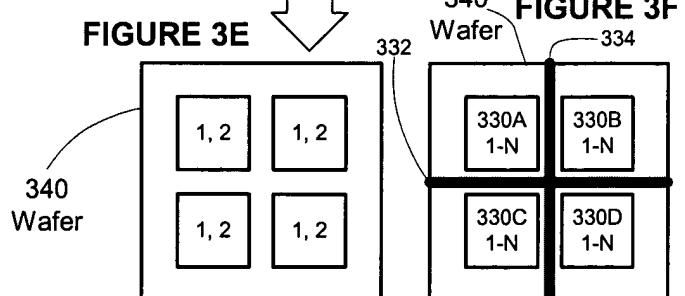
**FIGURE 2A**

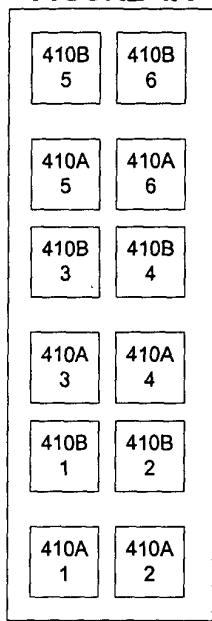
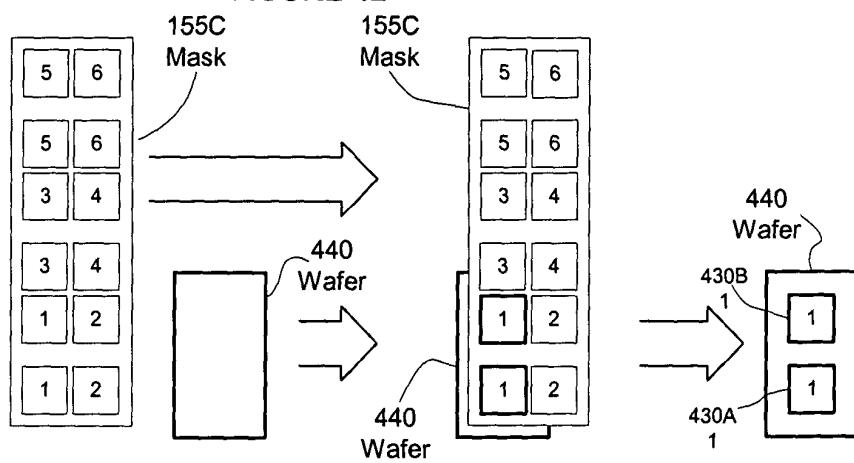


**FIGURE 2B  
(PRIOR ART)**

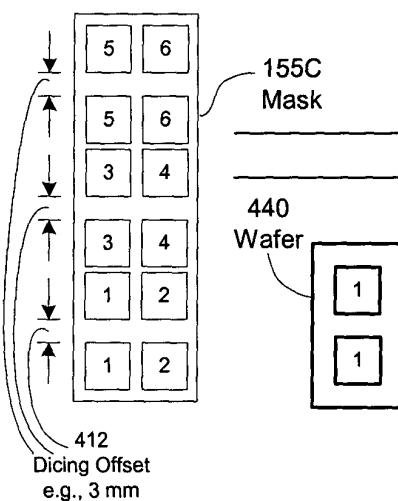
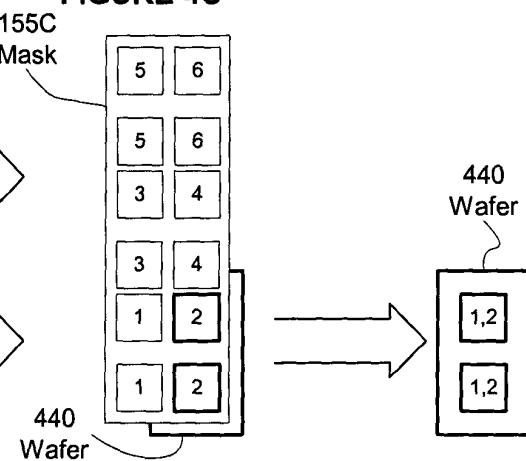
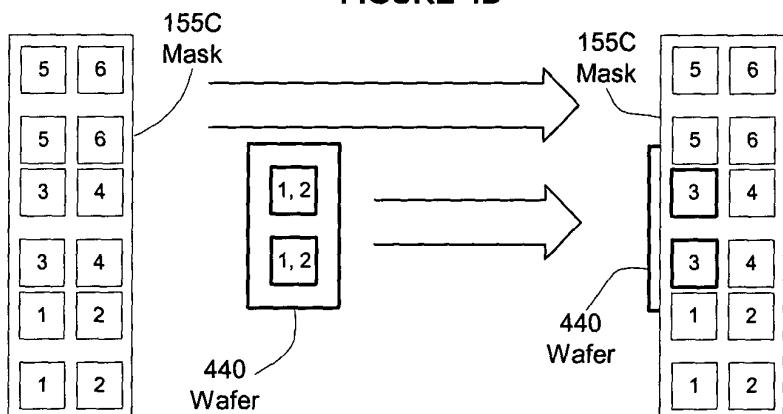
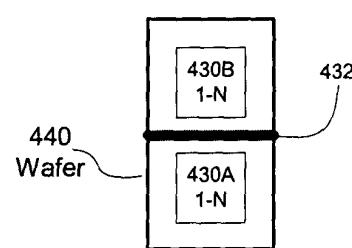


**FIGURE 2C**155A-1  
Mask240  
Wafer**FIGURE 2D**212  
Dicing Offset  
e.g., 3 mm**FIGURE 2G**155A-2  
Mask240  
Wafer**FIGURE 2H****FIGURE 2E**155A-N  
Mask240  
Wafer**FIGURE 2F (PRIOR ART)**

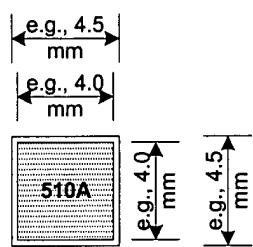
**FIGURE 3A****FIGURE 3B****FIGURE 3C****FIGURE 3C****FIGURE 3D****FIGURE 3E**

**FIGURE 4A****FIGURE 4B**

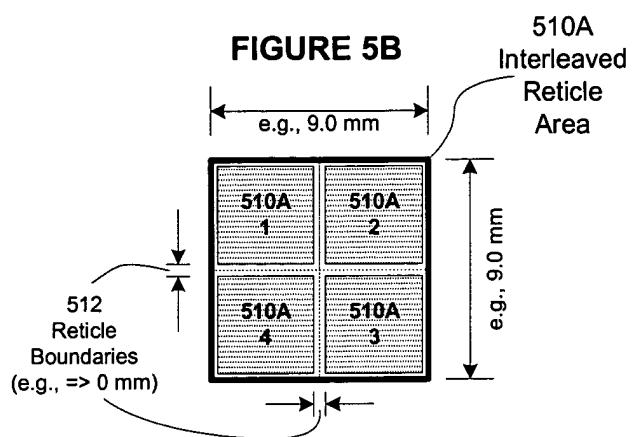
412  
Dicing Offset  
e.g., 3 mm

**FIGURE 4C****FIGURE 4D****FIGURE 4E**

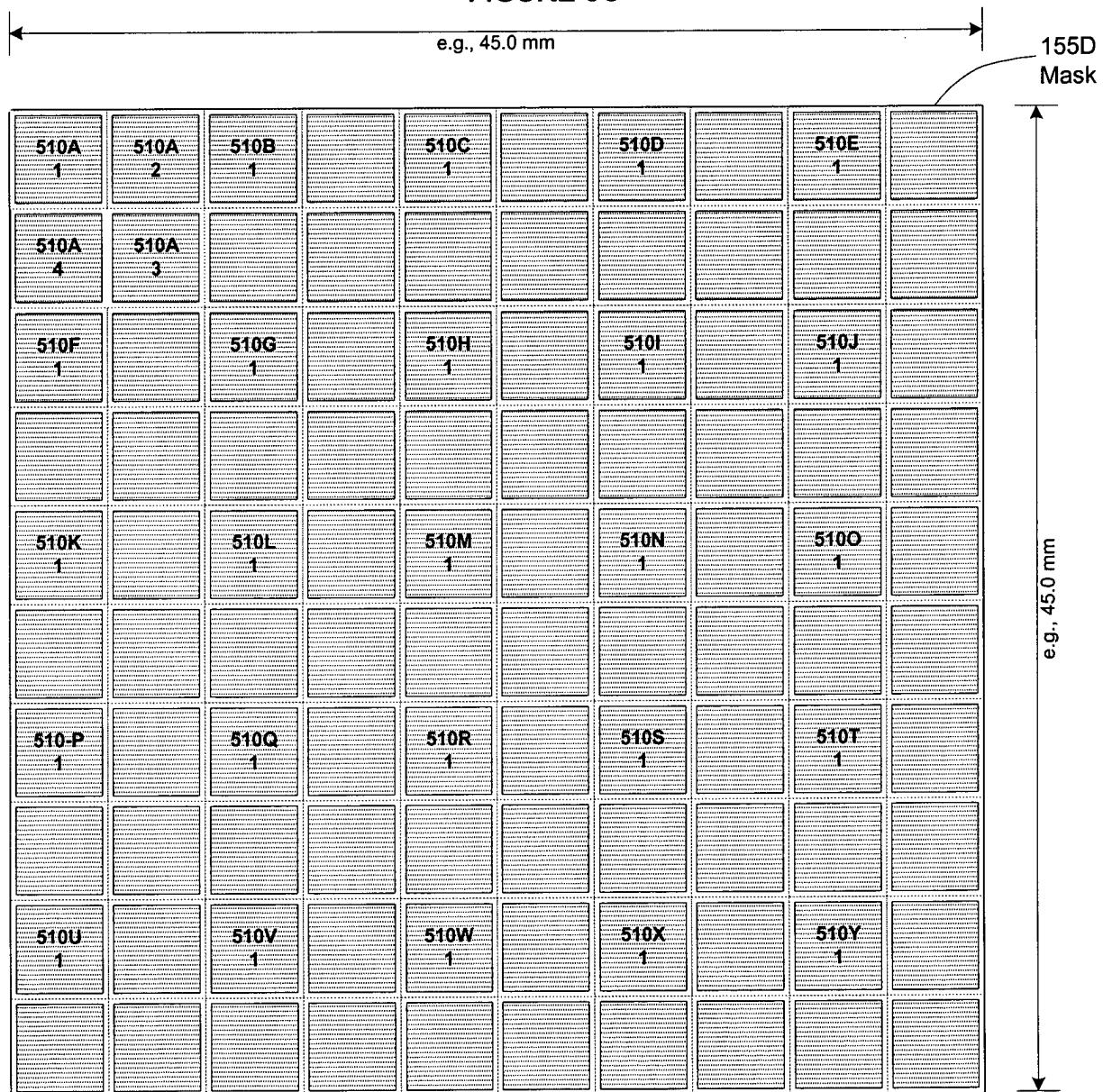
**FIGURE 5A**



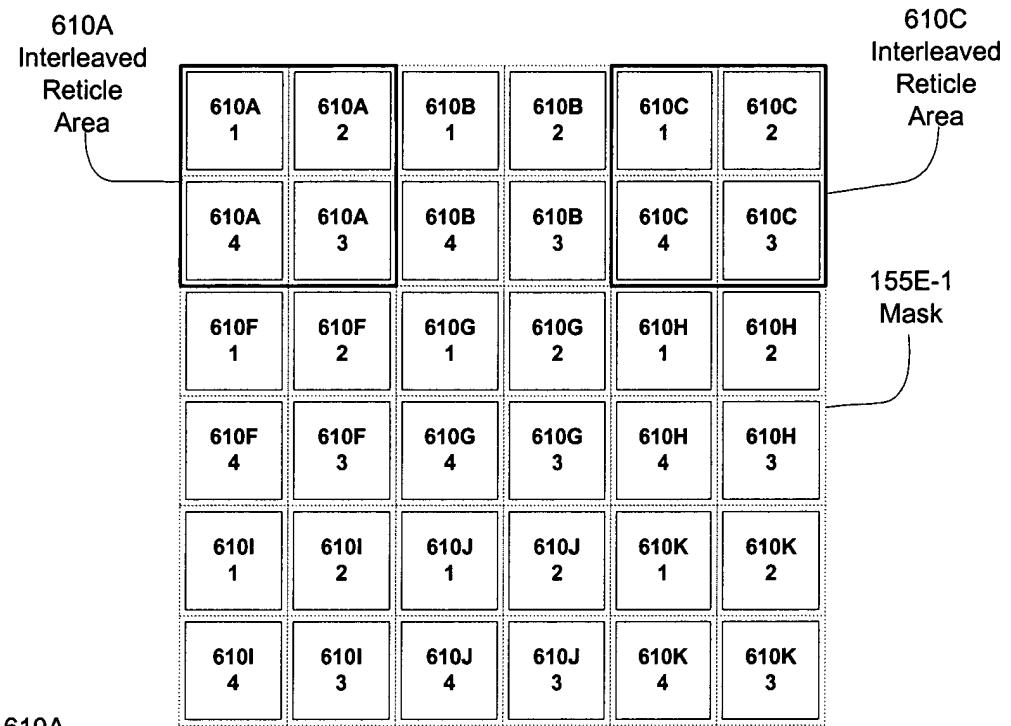
**FIGURE 5B**



**FIGURE 5C**

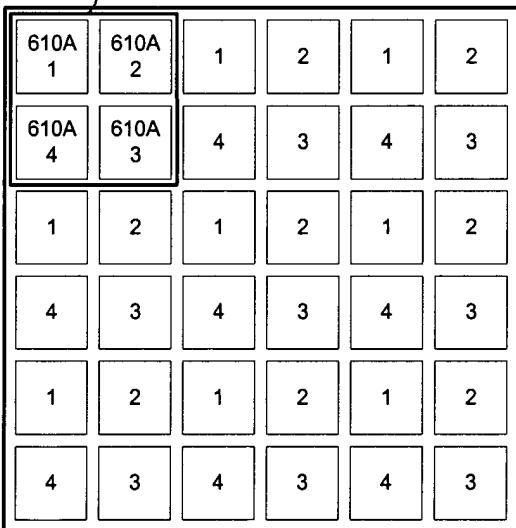


**FIGURE 6A**

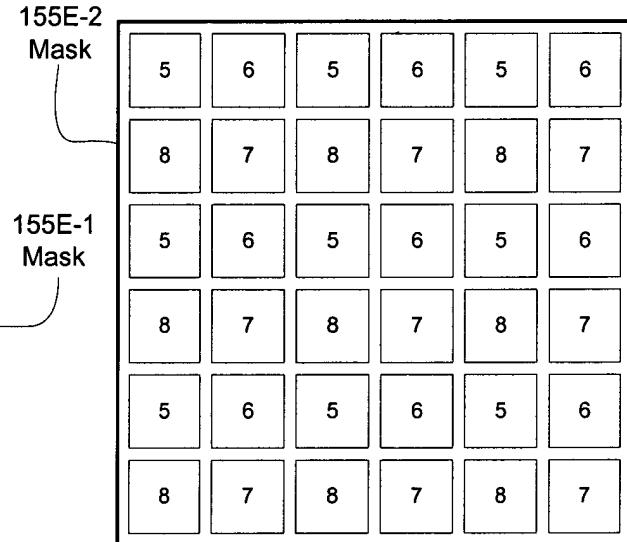


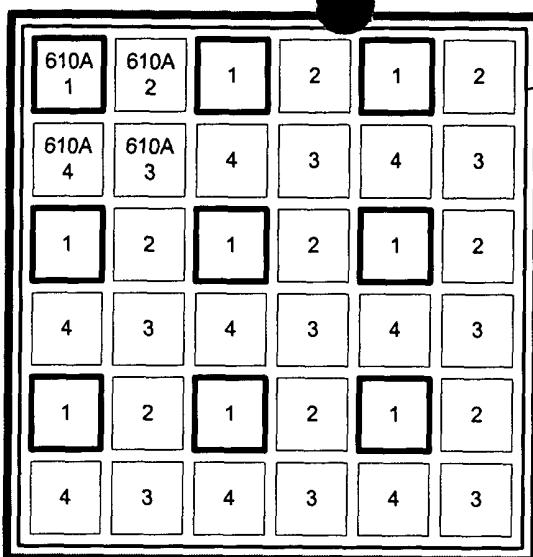
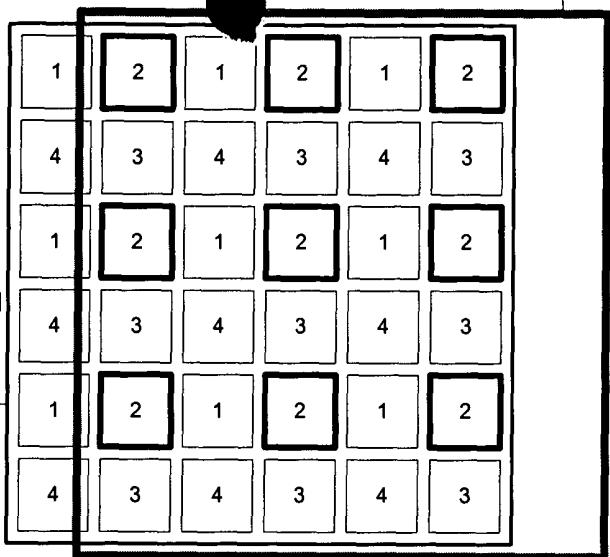
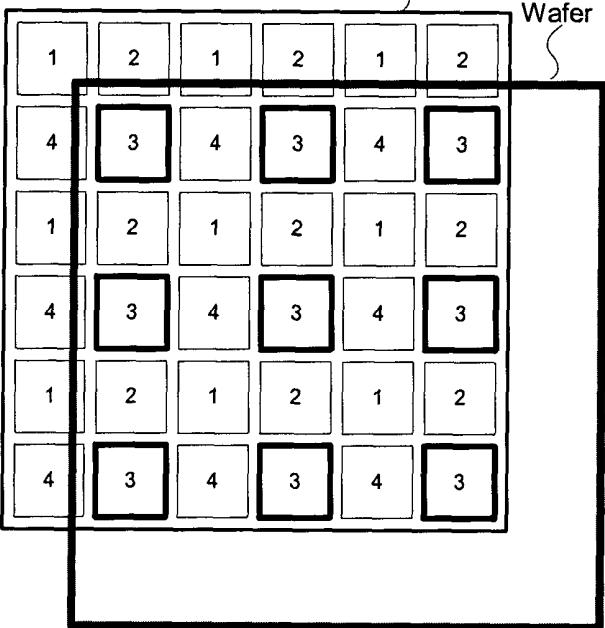
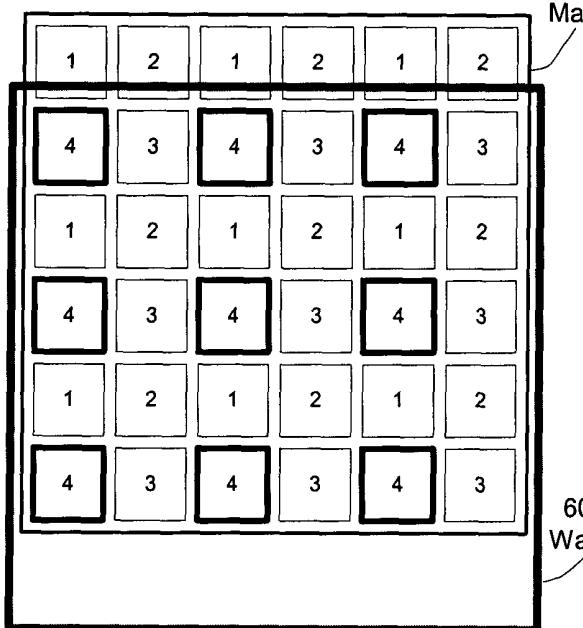
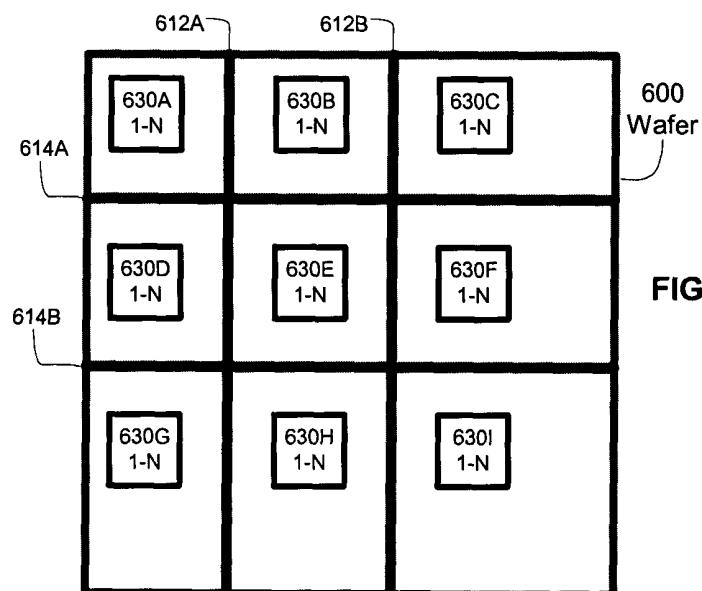
610A  
Interleaved  
Reticle  
Area

**FIGURE 6B**



**FIGURE 6C**



**FIGURE 6D - STEP 1**155E-1  
Mask**FIGURE 6E - STEP 2**600  
Wafer**FIGURE 6F - STEP 3**155E-1  
Mask600  
Wafer**FIGURE 6G - STEP 4**155E-1  
Mask600  
Wafer600  
Wafer**FIGURE 6H**

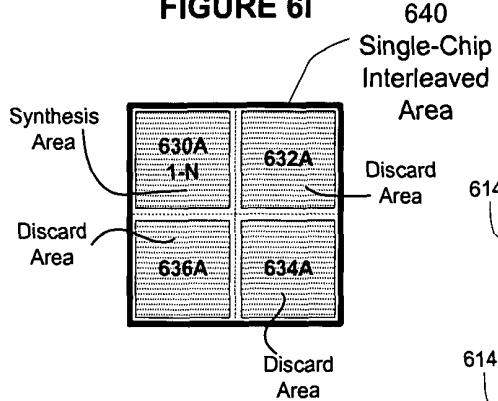
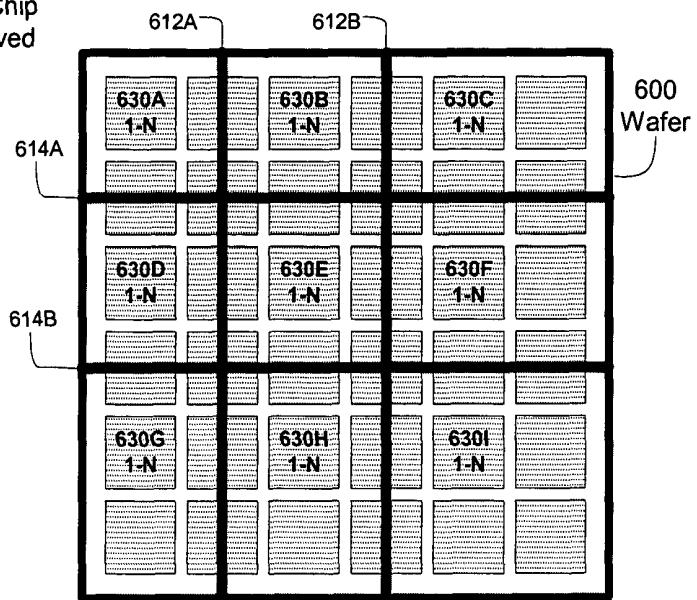
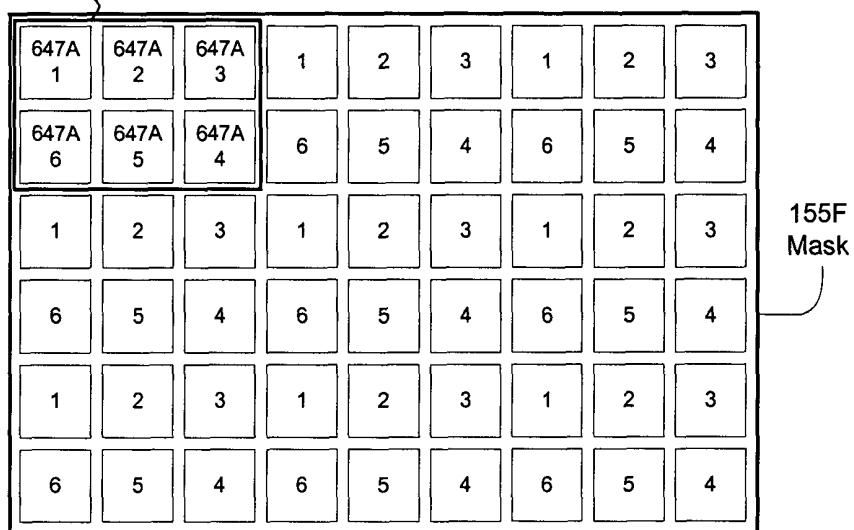
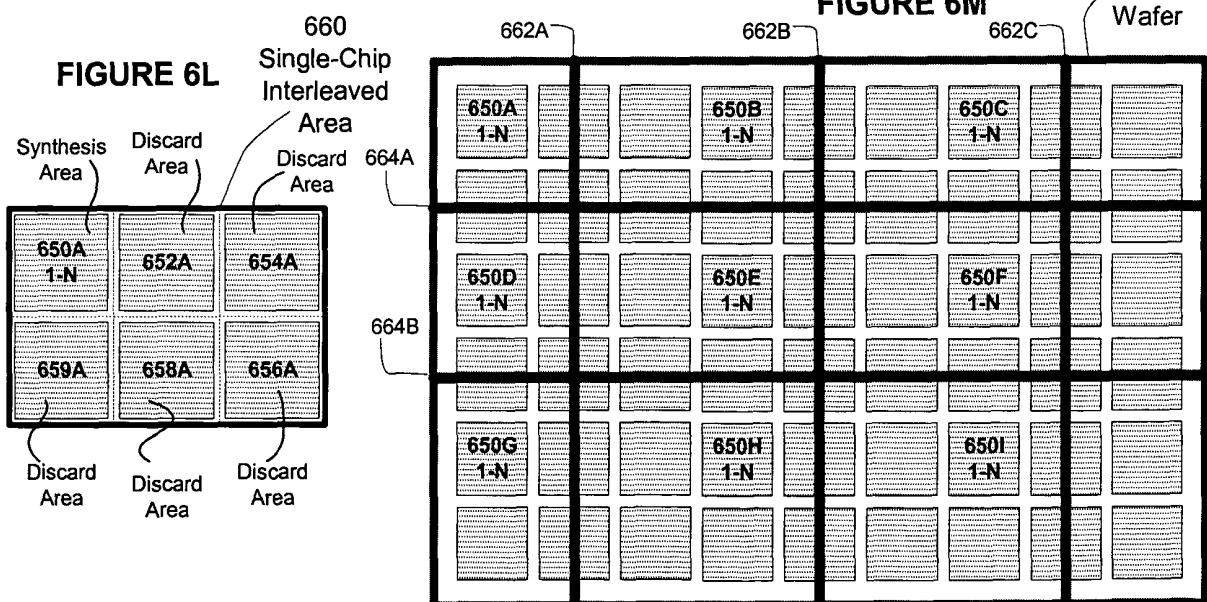
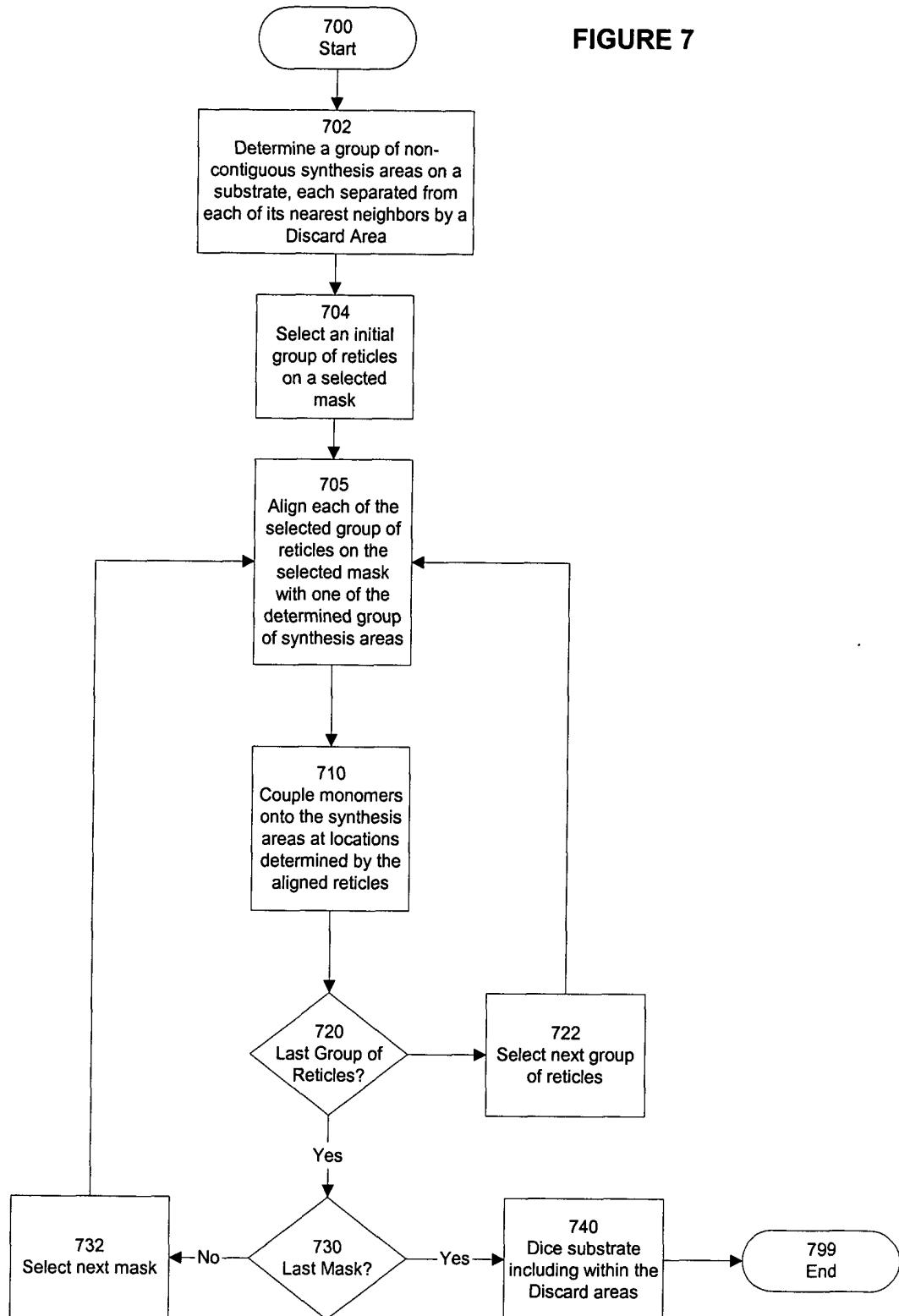
**FIGURE 6I****FIGURE 6J****FIGURE 6K****FIGURE 6M**

FIGURE 7



**FIGURE 8**

